

ABSTRACT OF THE DISCLOSURE

5 Provided herein is a method of improving the
planarity of a support plate of a susceptor for use during
deposition of a film of material onto a substrate comprising the
steps of reducing pressure in a hollow core of a shaft to a level
below atmospheric pressure; and reducing a pressure in the
deposition chamber to a level required for the deposition of the
10 film of material onto the substrate, where the pressure in the
hollow core of the shaft acts upon a lower surface of the support
plate connected to the shaft and interfacing with the hollow core
of the shaft and the pressure in the deposition chamber acts upon
an upper surface of the support plate adapted to support the
15 substrate thereby improving planarity. Also provided are a
susceptor and a method of depositing a film onto a substrate
affixed to the susceptor of the present invention.